

FORM PTO-1449 U.S. Department of Commerce Patent and Trademark Office List of Documents Cited by Applicant		Application No.:	10/523,948
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		First Named Inventor:	Hallahan et al.
		Group:	
		Examiner:	
		Attorney Docket No.:	1242/57 PCT/US

U.S. PATENT DOCUMENTS

Examiner Initial	Cite No.	Document Number	Publication Date	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, where relevant passages or relevant figures appear

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Examiner Initials	Cite No.	Include Author (in CAPITAL LETTERS), Title, Journal, Date, Pertinent Pages, Etc.	T
	1	International Search Report for corresponding PCT Appl. No. PCT/US03/25015 dated April 24, 2004.	
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SG	4	Database EMBASE on STN, (Columbus, OH, USA), No. 2001275912, GUPTA ET AL., "The ras radiation resistance pathway", <u>Cancer Research</u> , 61(10): 4278-4282, May 15, 2001.	
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/Shirley Gembeh/

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5/27/08

*Examiner Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.